

[10191/3399]

**REPLY UNDER 37 C.F.R. § 1.116
EXPEDITED PROCEDURE
GROUP ART UNIT 1765**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

10 NN ENTER

LV

1/19/07

Appl. No. : 10/691,108 Confirmation No. 4772
Applicant : Klaus BREITSCHWERDT
Filed : October 22, 2003
Title : DEVICE AND METHOD FOR ANISOTROPIC PLASMA ETCHING OF A SUBSTRATE, PARTICULARLY A SILICON ELEMENT
TC/A.U. : 1765
Examiner : Lan Vinh

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY UNDER 37 C.F.R. § 1.116

Sir:

In response to the Final Office Action of August 8, 2006, please amend the above-captioned application without prejudice as follows.

Amendments to the Claims are reflected in the listing of claims, which begins on page 2 of this paper

Remarks begin on page 4 of this paper.